

RPCVD (T-AIOx)

Designed to form an integrated AIOx and SiNx passivation on the rear side of solar cell to improve its efficiency.

SOLAR TECHNOLOGY CELL PROCESS MACHINE

Technical Specification

Format(mm)	6,020(W) x 7,630(L) x 3,730(H)
Weight(kg)	8,800 * 2
Gas Supply	SiH4, NH3, N2O, TMA, O2, H2O
Number of Chamber	10
Cycle Time(min)	41
Uptime(%)	97
Boat Capacity	416 wafers/Boat
Wafer Throughput	6,000 wafers with boat wafer 416
Cell Type	Monocrystalline, Multicrystalline Silicon wafers
Cell Size(mm)	M2(156*156) ~ M4(161.75*161.75)
Cell Thickness(um)	120 ~ 200(±20)
Process Temperature(°C)	200 ~ 500
Process Pressure(Torr)	0.5 ~ 3.0

Dimension

